

| Application/Control No. | Applicant(s)/Patent under Reexamination | |
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| 10/811,436 | CHOE, SWEE YEW | |
| Examiner | Art Unit | |
| Long Nguyen | 2816 | |

| | SEARCHED | | | | | |
|-------|--|--------|----------|--|--|--|
| Class | Subclass | Date | Examiner | | | |
| 327 | 199-205, 208, 210, 211, 212, 214, 215, 218, 219, 223, 225 | 4/7/05 | IN | | | |
| 326 | 95,97,98 | | J | | | |
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| INT | INTERFERENCE SEARCHED | | | | |
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| SEARCH NOTES (INCLUDING SEARCH STRATEGY) | | | | |
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